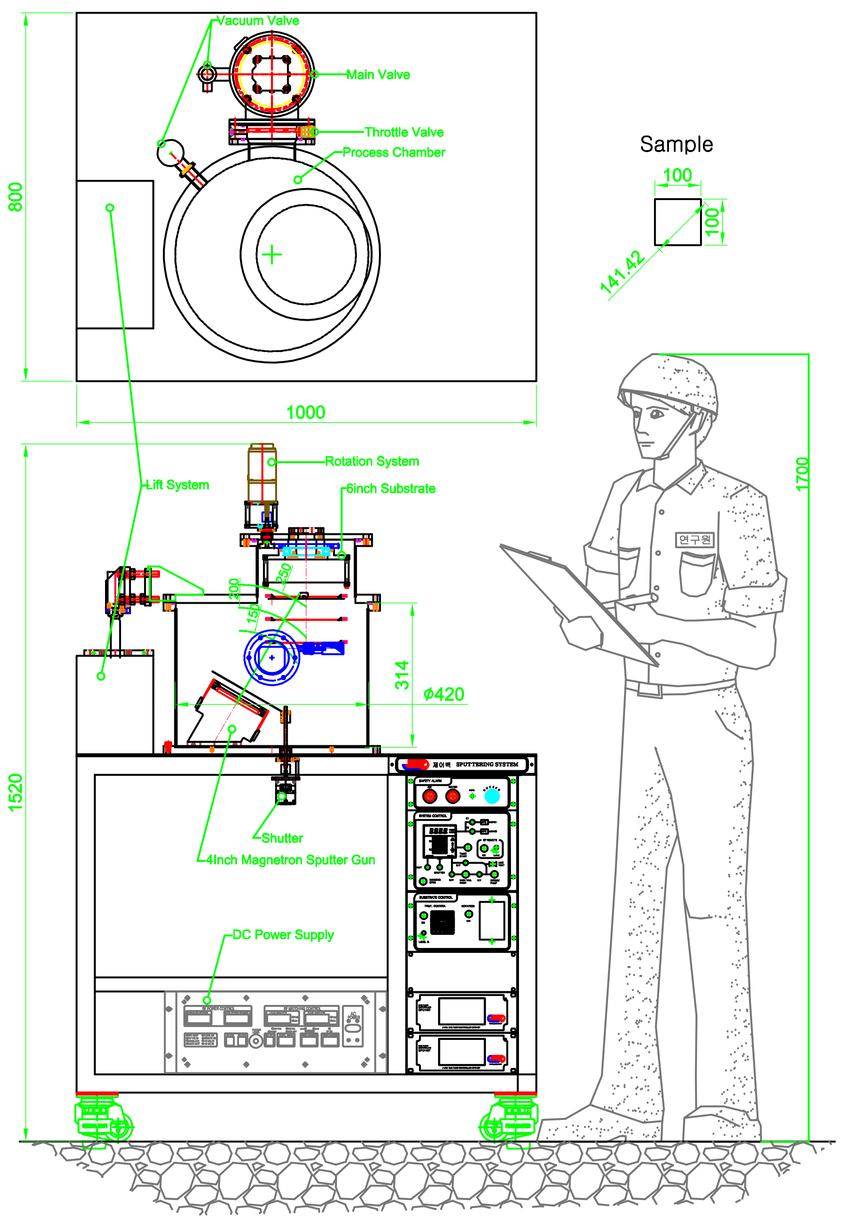

호서대학교 / 배 병 성 교수님연구실

1. Magnetron Sputtering Gun : 4Inch
2. Sample Size : 약 6inch (100mmX100mm)
3. Substrate Rotation : 0~20rpm
4. Substrate Moving : 150~250mm
5. DC Power Supply : 2Kw
6. Gus : Ar 100sccm / O2 30sccm
- * Auto Pressure Controll
- * Plasma Time(remote) Controll

* 실제 제작시 외형은 다를수 있습니다.

REV.	DATE.		RIVISER	BY	CKD
△	–				

NO.	PARTS NO	PARTS NAME	MATERIAL	Q'TY	REMARK
1					

J VACUUM TECHNOLOGY 제 이 벡

NAME: 전체도

DWN	MICHAEL JO	▽	25S~100S	DATE. 2018. 08.	Q'TY –	WT. –	KG
CKD		▽▽	6.3S~25S	DRAWING. NO.			REV.
APPD		▽▽▽	0.8S~6.3S	2018–호서대–진공증착기			0
SCALE		▽▽▽▽	0.8S 이하				

A₃ (297X420)